



Ofer Adan is the Head of Patterning Control Technology at Applied Materials. Adan has held various roles, leading solutions in metrology inspection and process control since 2001. Adan chaired SPIE Advanced Lithography's Metrology Inspection and Process Control conference. A steering committee member in the FCMN conference. Adan has been teaching a course on Advanced Concepts in Metrology Toolset Stability and Matching at SPIE. He also has several patents including the first patent on using high energy for SEM Overlay, and over 50 publications on metrology, inspection, process control, failure analysis, and fracture. Adan was awarded several best paper awards at various conferences among them the SPIE Diana Nyssonen Memorial Award. Adan received an

M.Sc. degree in electronic materials engineering from Ben Gurion University where he developed a failure criterion for crack propagation in a re-entrant angle under thermal loading and applied it to improve reliability of interfaces between interconnects and passivation layers in CMOS imaging devices.